

Rectangular Magnetron



Rectangular magnetron

Industry-leading high performance planar magnetrons

Gencoa planar rectangular magnetron fields combine robust design and the best plasma control to produce the best performance in the industry. Attention is given to ensuring long-life and trouble-free operation, with the optimized magnetic fields providing the best possible target use and target cleanliness.



Rectangular Magnetron

Gencoa have a well-established track record of providing critical components and technology for coating flexible substrates, architectural glass, solar cells, displays, touch screens and semiconductor wafers.

Our planar rectangular magnetrons combine low ownership cost, robust design and highly optimized magnetics to produce a reliable product delivering high performance. Careful attention is given to ensuring a long-life, trouble-free operation and excellent target use.

The integrated gas delivery system acts as a powerful mechanism for tuning deposition uniformity by employing single or multi-zone control. All cathodes are fitted with a diaphragm type cooling for high power operation without breaking a water seal during target changeover. Direct cooling is achievable with removal of the diaphragm.

Gencoa sources are configured with various power options such as DC, pulsed-DC, RF (up to 30kW) and HiPIMS.

A unique design incorporating zero-height anodes prevent short circuits during processes and reduce dust and defects in the coatings. Optional water-cooled anodes reduce the thermal impact on the substrate. All sources incorporate flange plate cooling as standard.

Depending on the application, Gencoa can configure individual cathodes to meet specific process requirements and limitations. We also offer OEM proprietary magnetron design and manufacture service, as well as refurbishments and upgrades of other manufacturers' cathodes.



Rectangular Vtech



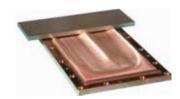
Rectangular magnetron with centre target clamp

Magnetic options

Target width (mm)	50	65	75	100	125	150	200	250	300	Typical target use
Balanced (SW)	•		•	•	•	•	•	•	•	25-30%
Unbalanced (PP)		•	•	•	•	•	•			25-30%
High Yield (HY)				•	•	•	•	•	•	40-50%
LOOP				•	•					25-40%
Metallizer (MZ)			•	•	•	•	•	•	•	50-60%
High Strength (HS)			•	•	•	•				18-22%
RF HY				•	•	•	•			35-45%
FFE HS				•	•	•				35-50%
VTech			•	•	•	•				25-40%



Used target (metalizer magnetics)



Used target (high yield magnetics)



Externally-mounted rectangular magnetron



Angled dual internal cantilever



Web coating configuration involving multiple rectangular magnetrons